

Supporting Information (SI) *for*:

**3D Self-assembled VS₄ Microspheres with High Pseudocapacitance as Highly
Efficient anodes for Na-ion Batteries**

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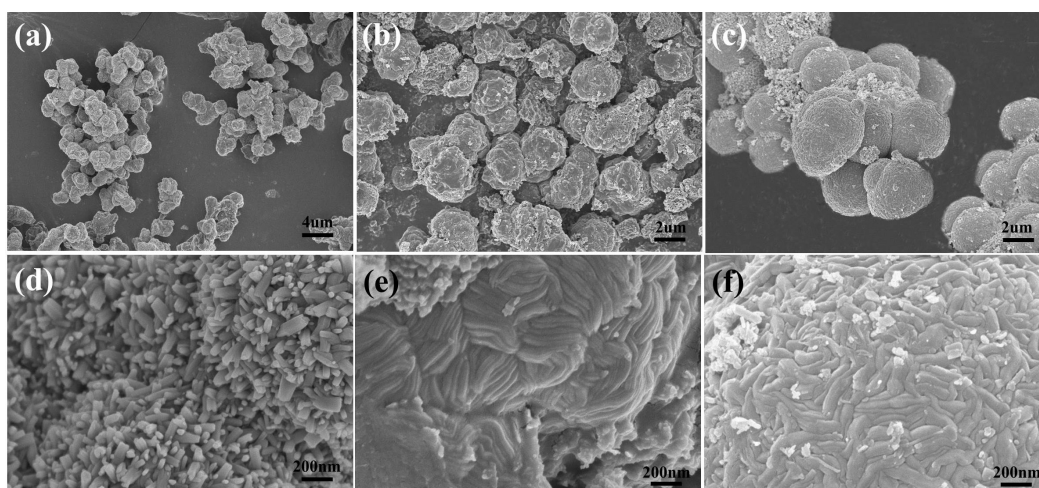
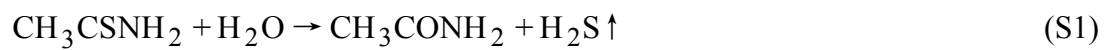
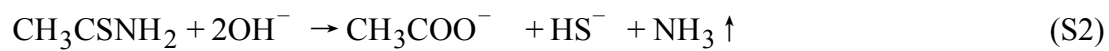


Fig. S1 SEM images of (a and d) VS₄-10, (b and e) VS₄-5 and (c and f) VS₄-3.

At lower pH value:



At higher pH value:



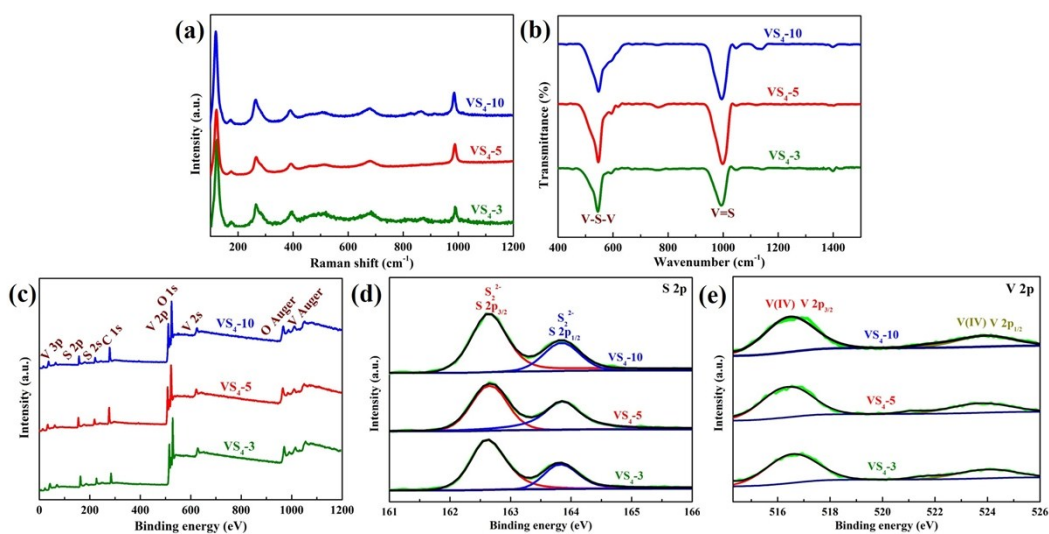


Fig. S2 (a) Raman spectra, (b) FTIR spectra, (c) Survey XPS spectra, High-resolution (d) S 2p and (e) V 2p XPS spectra of VS₄-10, VS₄-5 and VS₄-3.

As shown in Fig. S2(a), all Raman spectra appear almost identical with seven peaks located at 141, 191, 282, 406, 522, 689 and 992 cm⁻¹, which correspond to the bending and stretching vibrations of V-S bonds or their combination^{1, 2}. When compared to their FTIR database in Fig. S2(b), three VS₄ products show two very similar peaks at 547 and 995 cm⁻¹, corresponding to the ν (V-S-V) doubly bonded S²⁻ and the ν (V=S) terminal S stretches of VS₄, respectively^{3, 4}. In addition, it can be clearly seen from the survey XPS spectra in Fig. S2(c) that all the samples have similar elemental composition, and their atomic ratios of V:S are close to 1:4. As displayed in Fig. S2(d and e), three VS₄ products exhibit very similar high-resolution S 2p XPS spectra with two S₂²⁻ 2p peaks at 162.7 and 163.9 eV, and V 2p XPS spectra with two V⁴⁺ 2p peaks at 516.5 and 523.8 eV^{5, 6}.

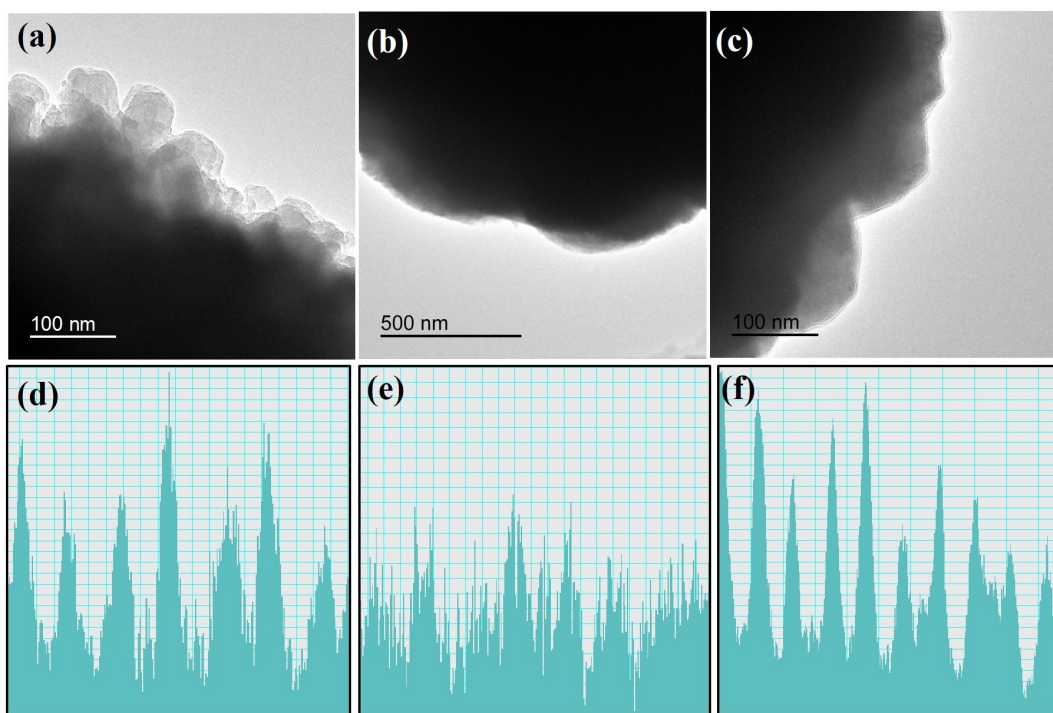


Fig. S3 High-magnification TEM images of (a) VS₄-10, (b) VS₄-5, (c) VS₄-3, and Histogram transform patterns of (d) VS₄-10, (e) VS₄-5, (f) VS₄-3 corresponding to HRTEM images in Fig. 4.

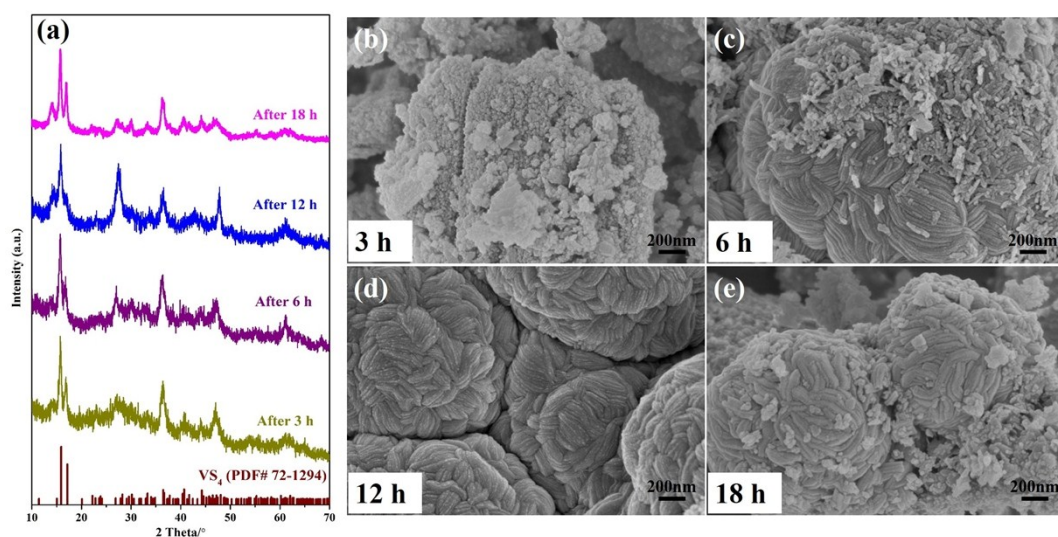


Fig. S4 (a) XRD patterns of the products collected after the hydrothermal reaction at pH=5 for different reaction times. SEM images of the products obtained at pH=5 for different reaction times: (b) 3 h, (c) 6 h, (d) 12 h and (e) 18 h.

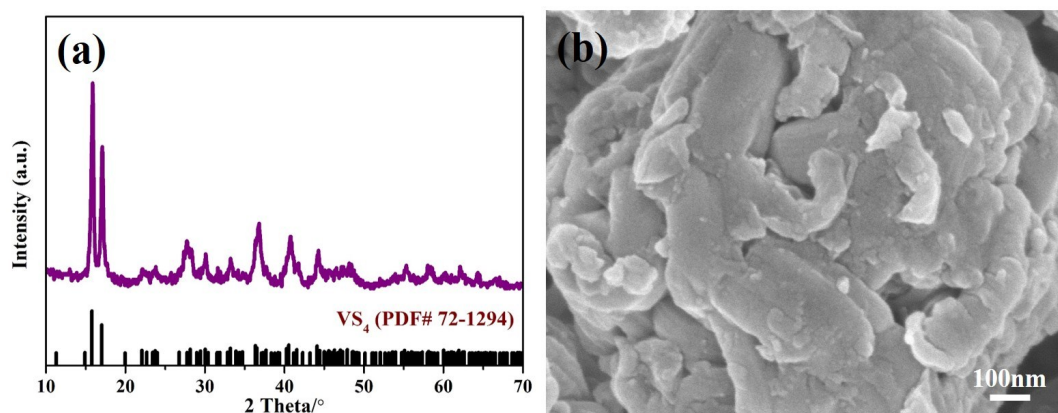


Fig. S5 (a) XRD pattern and (b) SEM image of the product obtained at pH=1 (1 g $NaVO_3$, 3.6 g C_2H_5NS , 180 °C, 24 h).

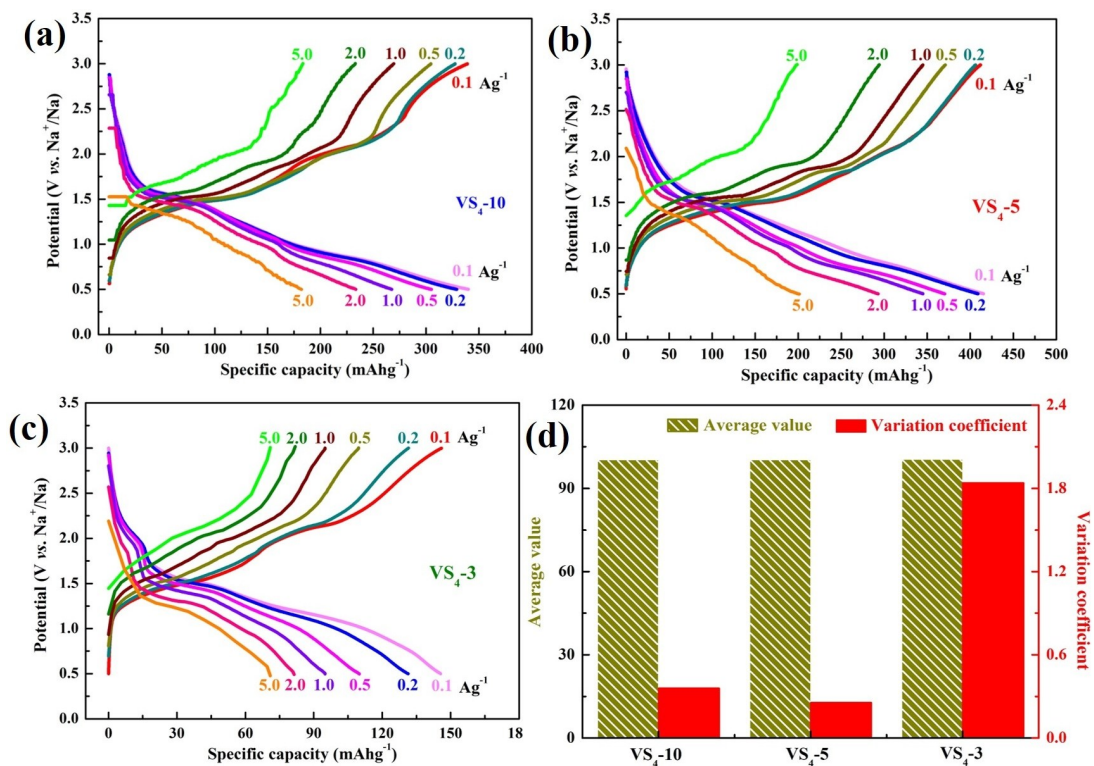


Fig. S6 Charge/discharge profiles of (a) $\text{VS}_4\text{-10}$, (b) $\text{VS}_4\text{-5}$ and (c) $\text{VS}_4\text{-3}$ electrode at various current densities from 0.1 to 5.0 Ag^{-1} . (d) Average values and variation coefficients of the CEs between the 70th and 300th cycle derived from Fig. 5(a).

Table S1 Electrochemical performance comparison of the as-prepared VS₄-5-based with other some V-based anode materials of SIBs.

Materials	Current density, Ag ⁻¹	Cycling capacity, mAhg ⁻¹ , (cycle number, n)	Rate capacity, mAhg ⁻¹ , (Current density, Ag ⁻¹)	Cut-off voltage (V)	Active material loading, mg·cm ²	Electrode composition	Ref
VS₄-5	0.2	412(300)	408(0.2), 370(0.5), 345(1.0), 293(2.0), 201(5.0)	0.5~3.0	0.8 ~ 1.2	8:1:1	This work
VS ₄ /rGO	0.5	149(100)	341(0.1), 267(0.3), 220(0.5), 192(0.8)	0.01~2.2	0.84~1.05	7:2:1	1
VS ₄ /GS	0.1	349.1(100)	314(0.1), 299(0.2), 277(0.5), 256(1.0), 234(2.0), 191(4.0)	0.3~3.0	~1.5	7:2:1	7
VS ₂	0.2	245(100)	252(0.1), 211(0.5), 201(1.0), 196(2.0), 203(5.0)	0.4~2.2	0.84~1.05	7:2:1	8
ce-VS ₂	1.0	109(100)	----	0.01~3.0	~1.0	7:2:1	9
VS ₂ @Na ₂ Ti ₂ O ₅	0.2	203(50)	233(0.1), 210(0.4), 161(1.0), 124(2.0), 75(4.0)	0.01~3.0	1.0~1.5	----	10
c-VS ₂ @VO OH	0.2	330(150)	424(0.1), 404(0.2), 356(0.5), 224(1.0), 140(2.0), 113(5.0)	0.5~3.0	0.6~1.0	8:1:1	11
VSe ₂ /C	0.1	467(50)	437(0.05), 375(0.1), 326(0.2), 309(0.5), 263(1.0), 132(2.0)	0~3.0	----	8:1:1	12

V ₂ O ₅	0.04	177(100)	200(0.04), 185(0.08), 157(0.16), 130(0.32), 122(0.64)	1.0~4.0	~0.88mg	8:1:1	¹³
VO ₂ /rGO	0.4	123(200)	196(0.04), 178(0.08), 160(0.16), 134(0.4), 108(0.8)	0.25~3.0	----	8:1:1	¹⁴
FeV ₂ S ₄	0.075	529(10)	548(0.075), 480(0.15), 372(0.375)	0~3.0	~3.0	8:1:1	¹⁵

The list of electrode composition ratio contains the active material, the conductive material and the binder.

----: The relevant data is not mentioned in the article.

Table S2 Charge/discharge plateau capacities and corresponding to plateau voltage ranges of VS₄-10, VS₄-5 and VS₄-3 electrode at the 180th cycle in Fig. 5(c).

Sample	VS ₄ -10	VS ₄ -5	VS ₄ -3
Discharge plateau capacity (mAhg ⁻¹)	139	132	94
Voltage range (V)	1.101~1.613	1.083~1.620	1.095~1.630
Total discharge capacity	304	393	204
Charge plateau capacity (mAhg ⁻¹)	151	166	88
Voltage range (V)	1.487~1.983	1.475~1.836	1.492~1.892
Total charge capacity	306	393	204

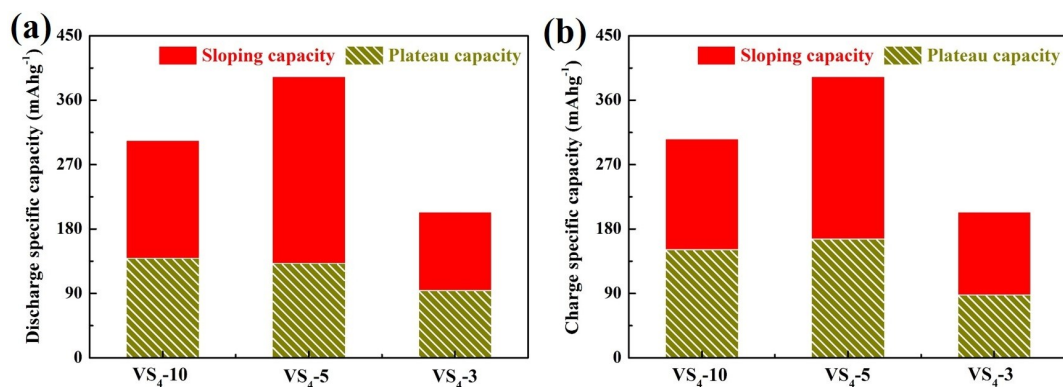


Fig. S7 Plateau capacities and sloping capacities of (a) discharge specific capacities and (b) charge specific capacities in Fig. 5(c) for VS₄-10, VS₄-5 and VS₄-3 electrode.

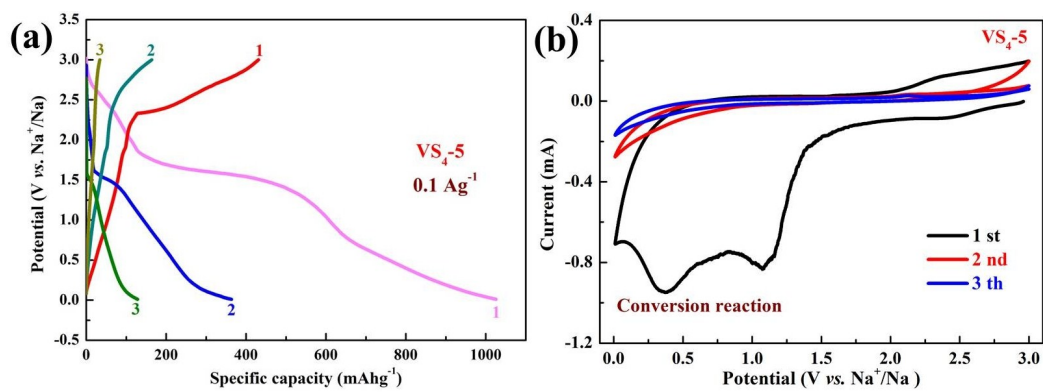


Fig. S8 (a) Charge/discharge profiles at 0.1 Ag⁻¹ and (b) CV curves at a scan rate of 0.2 mVs⁻¹ of VS₄-5 electrode.

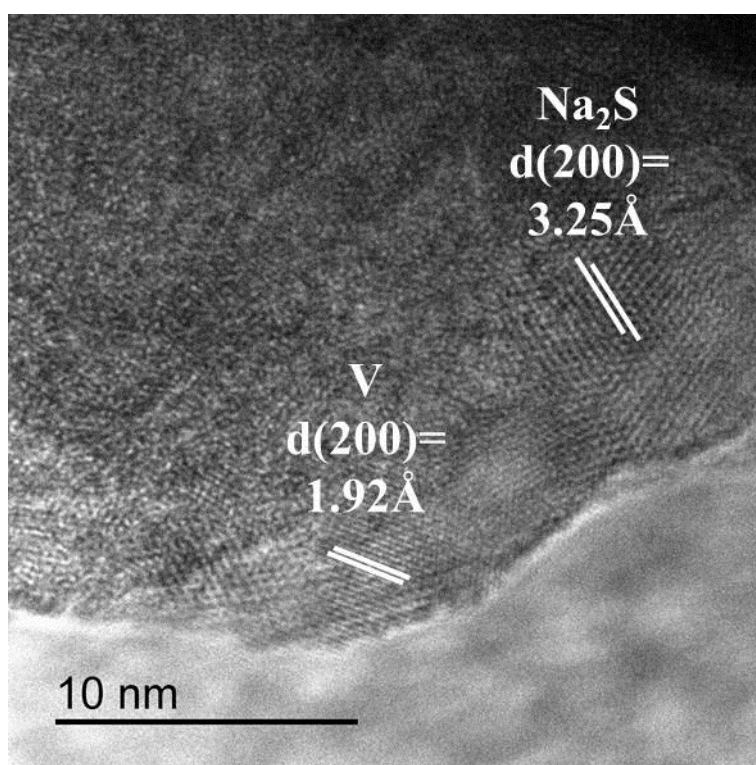


Fig. S9 HRTEM images of VS₄-5 electrode after discharged to 0.01 V at 0.02 Ag⁻¹.

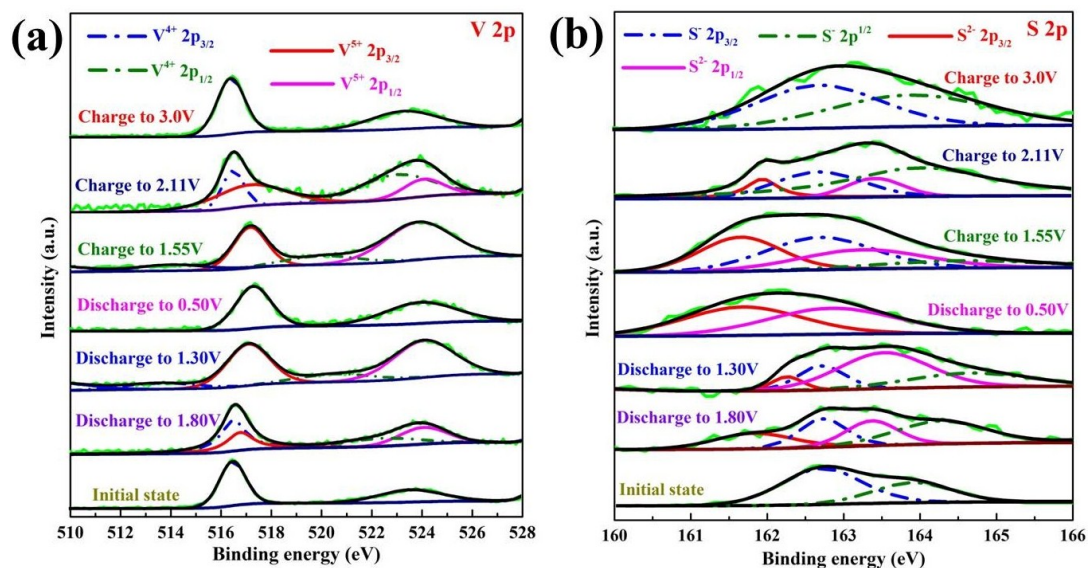


Fig. S10 High-resolution (a) V 2p and (b) S 2p XPS spectra of VS₄-5 electrode after discharging and charging to different potential states at 0.02 Ag⁻¹.

Table S3 Average valence of V and S, Number of Na⁺ and corresponding Specific capacity for VS₄-5 electrode after discharging and charging to different potential states at 0.02 Ag⁻¹.

Potential state	Average valence of V	Average valence of S	Number of Na ⁺	Specific capacity (mAhg ⁻¹)
Initial state	+4	-1	0	0
Discharge to 1.80V	+4.46	-1.36	0.98	243
Discharge to 1.30V	+4.80	-1.82	2.48	412
Discharge to 0.50V	+5	-2	3	675
Charge to 1.55V	+4.78	-1.52	1.3	-
Charge to 2.11V	+4.46	-1.19	0.3	-
Charge to 3.0V	+4	-1	0	-

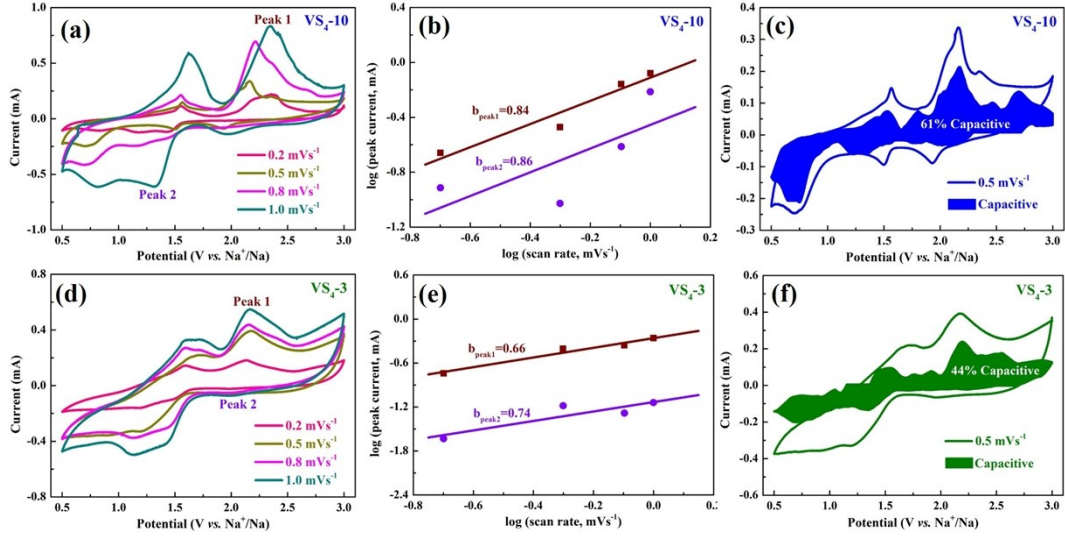


Fig. S11 CV curves of (a) VS₄-10 and (d) VS₄-3 electrode at different scan rates from 0.2 to 1.0 mVs⁻¹, The fitted lines and log (peak current) vs. log (scan rate) plots of (b) VS₄-10 and (e) VS₄-3 electrode at different oxidation and reduction states, and The capacitive contribution shown by the shaded region at 0.5 mVs⁻¹ for (c) VS₄-10 and (f) VS₄-3 electrode.

$$\log(I) = b \log(v) + \log(a) \quad (S3)$$

$$I(V) = k_c v + k_d v^{1/2} \quad (S4)$$

where a and b are adjustable parameters, I is the current (mA) and v is the scan rate (mVs⁻¹). The b -value is determined by the slop of $\log(v) - \log(i)$ plots. When b -value approaches to 0.5, the system is mainly controlled by a diffusion process, while b -value is closed to 1.0, the system is mainly controlled by a capacitive process¹⁶. The total current response ($I(V)$) at a fixed potential (V) can be divided into two parts including capacitive $I_c(k_c v)$ and diffusion-controlled $I_d(k_d v^{1/2})$ ^{17, 18}. The capacitive $I_c(k_c v)$ is composed of the faradaic contribution from the charge-transfer process occurring on the surface of electrode materials, referred to as pseudocapacitance; and the nonfaradaic contribution from double layer capacitive effect.

$$I_{(i)}(V) = k_c(V)v_i + k_d(V)v_i^{1/2} \quad i = 0.2, 0.5, 0.8, 1.0 \text{ mVs}^{-1}; \quad (\text{S5})$$

$$I_{(j)}(V) = k_c(V)v_j + k_d(V)v_j^{1/2} \quad j = 0.2, 0.5, 0.8, 1.0 \text{ mVs}^{-1}; i \neq j \quad (\text{S6})$$

$$k_{c(i-j)}(V) = \left(\frac{I_{(j)}(V)}{v_j^{1/2}} - \frac{I_{(i)}(V)}{v_i^{1/2}} \right) / (v_j^{1/2} - v_i^{1/2}) \quad (\text{S7})$$

$$k_{d(i-j)}(V) = \left(\frac{I_{(j)}(V)}{v_j} - \frac{I_{(i)}(V)}{v_i} \right) / (v_j^{-1/2} - v_i^{-1/2}) \quad (\text{S8})$$

$$k_c(V) = (k_{c(0.2-0.5)}(V) + k_{c(0.2-0.8)}(V) + k_{c(0.2-1.0)}(V) + k_{c(0.5-0.8)}(V) + k_{c(0.5-1.0)}(V) + k_{c(0.8-1.0)}(V)) / 6 \quad (\text{S9})$$

$$k_d(V) = (k_{d(0.2-0.5)}(V) + k_{d(0.2-0.8)}(V) + k_{d(0.2-1.0)}(V) + k_{d(0.5-0.8)}(V) + k_{d(0.5-1.0)}(V) + k_{d(0.8-1.0)}(V)) / 6 \quad (\text{S10})$$

$$I_{c(0.5)}(V) = \frac{k_c(V)}{k_c(V) + k_d(V) * 0.5^{-0.5}} I_{(0.5)}(V) \quad (\text{S11})$$

where $I_{(i)}(V)$ is the total current response at a fixed potential (V) and a fixed scan rate (i). $I_{(j)}(V)$ is the total current response at a fixed potential (V) and a fixed scan rate (j). v_i and v_j are the scan rate. $I_{c(0.5)}(V)$ is the capacitive current response at a fixed potential (V) and a fixed scan rate of 0.5 mVs⁻¹. $I_{(0.5)}(V)$ is the total current response at a fixed potential (V) and a fixed scan rate of 0.5 mVs⁻¹.

Table S4 Resistance values simulated from modeling the experimental impedance (Fig. 8(a)) using the equivalent circuit shown in the insets in the bottom right of Fig. 8(a).

Samples	R_s (Ω)	$R_f + R_{ct}$ (Ω)	$\theta(^{\circ})$
VS ₄ -10	49.8	53.4	70.5
VS ₄ -5	30.5	12.5	76.8
VS ₄ -3	48.8	156.6	43.5

R_s is the electrolyte resistance. R_f is the SEI film resistance. R_{ct} is the charge-transfer resistance from electrolyte to active materials. θ is the angle of the straight line at low frequency.

$$T_{sc} = (t_c + t_d)/(Q_c + Q_d) \quad (S12)$$

where T_{sc} is the charge/discharge time per unit specific capacity. t_c , t_d , Q_c and Q_d are the charge time, discharge time, charge specific capacity and discharge specific capacity at a fixed cycle.

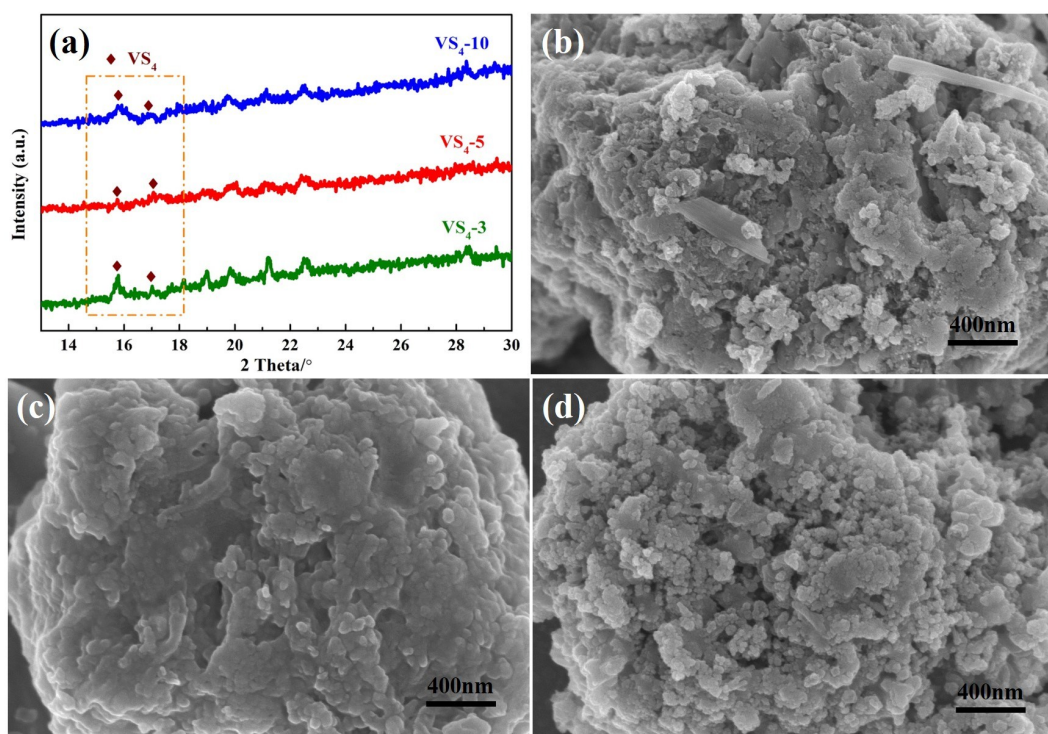


Fig. S12 (a) XRD patterns and SEM images of (b) VS₄-10, (c) VS₄-5 and (d) VS₄-3 after the rate and cycling tests.

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